



micro resist
technology

— CERTIFICATE OF ANALYSIS AND QUALITY FOR —

DEVELOPER

ma-D 533/S

Lot No.: 51925

Manufactured: 04/11/2025
(dd/mm/yyyy)

Expiration: 03/11/2026
(dd/mm/yyyy)

	Unit	Specification	Result
<u>Developer solution</u>			
Appearance		clear, colourless liquid	conforms
Odour		amine- like	conforms
Density at 20 °C	DMA 500	[g/cm ³]	1.000 ± 0.002
Total alkaline normality		[mol/l]	0.363 ± 0.011
<u>Lithographic check</u>			
Developing time t_0 for FT = 1.2 µm, ma-N 1410 # 25725	[s]	35 ± 5	30
Developing time t_0 for generation of an undercut of 0.65 ± 0.10 µm for FT = 1.20 µm, determined at a pattern size of 50 µm	[s]	65 ± 5	65
Undercut for FT = 1.2 µm for 65 s, determined at a pattern size of 50 µm	[µm]	0.65 ± 0.10	0.65
Critical dimension CD for FT = 1.2 µm	[µm]	50.0 ± 1.5	50.0

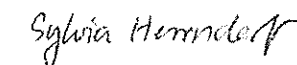
All lithographic data have been obtained using a Suss MA 56 mask aligner.
The data above are certified by


Britt Wiesner
Production manager


Marina Heinrich
Lithography manager

Confidential

We declare to be the original manufacturer of the product listed above.
We provide a guarantee for the product listed above for 12 months, if stored in the original sealed bottle.


Dr. Sylvia Herndorf
Quality Manager

The values stated in this certificate were determined thoroughly to the best of our knowledge. Changes in quality are possible due to incorrect handling or storage. We have no influence on these changes. Therefore, this certificate has no legal relevance.